



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|------------------------------|---|--------------------------------------|
| In re Patent Application of |) | Attorney Docket No.: TSUK0005 |
| |) | Confirmation No.: 5149 |
| Tatsuo CHIBA et al. |) | |
| |) | Group Art Unit: 1756 |
| Serial No.: 10/018,690 |) | |
| |) | Examiner: Chacko-Davis, Daborah |
| Filed: December 20, 2001 |) | |
| |) | |
| For: PHOTSENSITIVE ELEMENT, |) | Date: January 19, 2005 |
| PHOTSENSITIVE ELEMENT ROLL, |) | |
| PROCESS FOR THE PREPARATION |) | |
| OF RESIST PATTERN USING THE |) | |
| SAME, RESIST PATTERN, RESIST |) | |
| PATTERN LAMINATED |) | |
| SUBSTRATE, PROCESS FOR THE |) | |
| PREPARATION OF WIRING |) | |
| PATTERN AND WIRING PATTERN |) | |

AMENDMENT (C)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the non-final Office Action dated July 20, 2004, Applicants respectfully request reconsideration, under 37 C.F.R. § 1.111, of the application identified above as follows:

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.